



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Kei YOSHIKAWA et al.

Application No.: 09/662,219

Filed: September 14, 2000

For: PATTERN CORRECTING METHOD
OF MASK FOR MANUFACTURING A
SEMICONDUCTOR DEVICE AND
RECORDING MEDIUM HAVING
RECORDED ITS PATTERN
CORRECTING METHOD

Group Art Unit: 2623

Examiner: S. Ahmed

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Technology Center 2600

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

PETITION FOR EXTENSION OF TIME

Applicants hereby petition for a one-month extension of time to reply to the Office Action of July 14, 2003. A fee of \$110.00 is enclosed.

Please grant any extensions of time required to enter this response and charge any additional required fees to our deposit account 06-0916.

Respectfully submitted,

**FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.**

By: _____

D. Kent Stier
Reg. No. 50,640
(404) 653-6559

Dated: November 6, 2003

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FINNEGAN
HENDERSON
FARABOW
GARRETT &
DUNNER LLP

1300 I Street, NW
Washington, DC 20005
202.408.4000
Fax 202.408.4400
www.finnegan.com